

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	1	("6814814").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/10/10 19:52
S2	1	("7063094").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/10/11 09:26
S3	2261	(134/1).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/10/11 09:26
S4	2845	(134/2).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/10/11 09:26
S5	2693	(134/3).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/10/11 09:27
S6	1876	(134/6).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/10/11 09:27
S7	2049	(134/26).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/10/11 09:27
S8	506	(134/27).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/10/11 09:27
S9	1255	(134/28).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/10/11 09:27
S10	1036	(134/29).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/10/11 09:27
S13	995	S3 and ((clean\$4 or etch\$4 or treat\$4 or rins\$4) same (substrate or wafer or semiconductor or electronic))	US-PGPUB; USPAT; USOCR	OR	ON	2007/10/11 09:30
S14	1392	S4 and ((clean\$4 or etch\$4 or treat\$4 or rins\$4) same (substrate or wafer or semiconductor or electronic))	US-PGPUB; USPAT; USOCR	OR	ON	2007/10/11 09:29
S15	913	S5 and ((clean\$4 or etch\$4 or treat\$4 or rins\$4) same (substrate or wafer or semiconductor or electronic))	US-PGPUB; USPAT; USOCR	OR	ON	2007/10/11 09:29
S16	543	S6 and ((clean\$4 or etch\$4 or treat\$4 or rins\$4) same (substrate or wafer or semiconductor or electronic))	US-PGPUB; USPAT; USOCR	OR	ON	2007/10/11 09:29
S17	89	S8 and ((clean\$4 or etch\$4 or treat\$4 or rins\$4) same (substrate or wafer or semiconductor or electronic))	US-PGPUB; USPAT; USOCR	OR	ON	2007/10/11 09:29

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S18	408	S9 and ((clean\$4 or etch\$4 or treat\$4 or rins\$4) same (substrate or wafer or semiconductor or electronic))	US-PGPUB; USPAT; USOCR	OR	ON	2007/10/11 09:29
S19	1065	S7 and ((clean\$4 or etch\$4 or treat\$4 or rins\$4) same (substrate or wafer or semiconductor or electronic))	US-PGPUB; USPAT; USOCR	OR	ON	2007/10/11 09:29
S20	270	S10 and ((clean\$4 or etch\$4 or treat\$4 or rins\$4) same (substrate or wafer or semiconductor or electronic))	US-PGPUB; USPAT; USOCR	OR	ON	2007/10/11 09:29
S21	337	"134"/\$.ccls. and ((rub\$4 or scrub\$4 or wip\$4 or brush\$3) same acid same (substrate or wafer or semiconductor or electronic))	US-PGPUB; USPAT; USOCR	OR	ON	2007/10/11 09:54
S22	221	"134"/\$.ccls. and ((rub\$4 or scrub\$4 or wip\$4 or brush\$3) same alcohol same (substrate or wafer or semiconductor or electronic))	US-PGPUB; USPAT; USOCR	OR	ON	2007/10/11 09:56
S23	55	"134"/\$.ccls. and ((rub\$4 or scrub\$4 or wip\$4 or brush\$3) same acid same alcohol same (substrate or wafer or semiconductor or electronic))	US-PGPUB; USPAT; USOCR	OR	ON	2007/10/11 10:47
S24	12	"134"/\$.ccls. and ((rub\$4 or scrub\$4 or wip\$4 or brush\$3) same ketone same alcohol same (substrate or wafer or semiconductor or electronic))	US-PGPUB; USPAT; USOCR	OR	ON	2007/10/11 10:29
S25	40	shih-hong.in.	US-PGPUB; USPAT; USOCR	OR	ON	2007/10/11 10:31
S27	13	chen-anthony.in.	US-PGPUB; USPAT; USOCR	OR	ON	2007/10/11 10:35
S28	0	tan-sok.in.	US-PGPUB; USPAT; USOCR	OR	ON	2007/10/11 10:30
S29	5	hwang-stephen.in.	US-PGPUB; USPAT; USOCR	OR	ON	2007/10/11 10:35
S30	17	daugherty-john.in.	US-PGPUB; USPAT; USOCR	OR	ON	2007/10/11 10:35
S31	11	morel-bruno.in.	US-PGPUB; USPAT; USOCR	OR	ON	2007/10/11 10:35
S32	19	"134"/\$.ccls. and ((clean\$4 or etch\$4 or treat\$4 or rins\$4) same acetone same (hydrogen near2 peroxide) same (substrate or wafer or semiconductor or electronic))	US-PGPUB; USPAT; USOCR	OR	ON	2007/10/11 10:49